



503.34403CV4

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): MASUDA, et al
Serial No.: 09/421,043 (CPA)
Filed: October 20, 1999
For: PLASMA ETCHING APPARATUS AND PLASMA ETCHING METHOD
Group: 1763
Examiner: L. Alejandro

#11B
5/23/01
mw

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

May 21, 2001

Sir:

The following preliminary amendments and remarks respectfully submitted in connection with the above-identified application.

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IN THE CLAIMS:

Please cancel claims 1-12 without prejudice or disclaimer of the subject matter thereof, and add the following claims in lieu thereof:

BI --13. A plasma etching apparatus including a vacuum vessel as evacuated by an evacuation system, gas supply means for supplying an etching gas into the vacuum vessel, an electrostatic chucking device C for holding thereon a sample to